

Docket Number: 081468-0308272
Client Reference: P-1515.010-US



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re the Application of VAN DER ZOUW, Gerbrand	Confirmation No.: 1762
Application No.: 10/776,640	Group Art Unit: 2851
Filed: February 12, 2004	Examiner: NGYUYEN, H.
For: LITHOGRAPHIC DEVICE AND METHOD FOR WAFER ALIGNMENT WITH REDUCED TILT SENSITIVITY	

March 22, 2005

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COMMENTS ON STATEMENT OF REASONS FOR ALLOWANCE

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Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Applicants confirm with appreciation the receipt of the Notice of Allowability for this application. In reply to the Examiner's Statement of Reasons for Allowance, Applicants respectfully note that patentability is based on the subject matter of the claims as a whole. That is, the patentability of the claims rests on the combination of recited elements and limitations. As such, Applicants respectfully submit that no one element or limitation in particular should be deemed to impart to or be required for patentability of the claims.

Further, Applicants respectfully submit that independent apparatus claim 1, independent method claims 10 and 14, and independent alignment system claim 10 are all separately patentable from each other and solely for the subject matter specifically recited as a whole in each of those claims.

Respectfully submitted,

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